

# INTERNATIONAL STANDARD



---

**Semiconductor devices – Micro-electromechanical devices –  
Part 36: Environmental and dielectric withstand test methods for MEMS  
piezoelectric thin films**

INTERNATIONAL  
ELECTROTECHNICAL  
COMMISSION

---

ICS 31.080.99; 31.140

ISBN 978-2-8322-6720-2

<p><b>Warning! Make sure that you obtained this publication from an authorized distributor.</b></p>
---

## CONTENTS

FOREWORD.....	3
INTRODUCTION.....	5
1 Scope.....	6
2 Normative references .....	6
3 Terms and definitions .....	6
4 Testing procedure.....	6
4.1 General.....	6
4.2 Initial measurements.....	7
4.3 Tests .....	7
4.3.1 DUT setup and environmental conditions.....	7
4.3.2 Test duration .....	7
4.3.3 Number of tests and number of DUTs .....	7
4.4 Post treatment .....	8
4.5 Final measurements.....	8
5 Environmental and dielectric withstand testing.....	8
5.1 Environmental testing .....	8
5.1.1 General .....	8
5.1.2 High temperature bias test.....	9
5.1.3 High temperature and high humidity bias test .....	9
5.1.4 High temperature storage .....	9
5.1.5 Low temperature storage .....	10
5.1.6 High temperature and high humidity storage .....	10
5.1.7 Soldering heat test .....	10
5.1.8 Temperature cycling test .....	11
5.2 Dielectric withstand testing .....	12
Annex A (informative) Report of test results .....	14
A.1 General.....	14
A.2 Environmental test .....	14
A.3 Dielectric withstand test .....	14
Bibliography.....	16
Figure 1 – Flow of the testing procedure .....	7
Figure 2 – Temperature profile for reflow soldering with lead-free solder .....	11
Figure 3 – Temperature profile of the temperature cycling test.....	12
Figure 4 – Example of a dielectric withstand test circuit for DC voltage .....	13
Figure A.1 – I-V measurement .....	15
Figure A.2 – Optical image of top electrodes before and after breakdown .....	15
Table 1 – Selectable test conditions.....	9
Table 2 – Selectable test conditions.....	10
Table 3 – Soldering heat test condition .....	10
Table 4 – Conditions of temperature profile for reflow soldering with lead-free solder .....	11
Table A.1 – High-temperature test .....	14
Table A.2 – Dielectric withstand test .....	15

## INTERNATIONAL ELECTROTECHNICAL COMMISSION

**SEMICONDUCTOR DEVICES –  
MICRO-ELECTROMECHANICAL DEVICES –****Part 36: Environmental and dielectric withstand test methods  
for MEMS piezoelectric thin films**

## FOREWORD

- 1) The International Electrotechnical Commission (IEC) is a worldwide organization for standardization comprising all national electrotechnical committees (IEC National Committees). The object of IEC is to promote international co-operation on all questions concerning standardization in the electrical and electronic fields. To this end and in addition to other activities, IEC publishes International Standards, Technical Specifications, Technical Reports, Publicly Available Specifications (PAS) and Guides (hereafter referred to as "IEC Publication(s)"). Their preparation is entrusted to technical committees; any IEC National Committee interested in the subject dealt with may participate in this preparatory work. International, governmental and non-governmental organizations liaising with the IEC also participate in this preparation. IEC collaborates closely with the International Organization for Standardization (ISO) in accordance with conditions determined by agreement between the two organizations.
- 2) The formal decisions or agreements of IEC on technical matters express, as nearly as possible, an international consensus of opinion on the relevant subjects since each technical committee has representation from all interested IEC National Committees.
- 3) IEC Publications have the form of recommendations for international use and are accepted by IEC National Committees in that sense. While all reasonable efforts are made to ensure that the technical content of IEC Publications is accurate, IEC cannot be held responsible for the way in which they are used or for any misinterpretation by any end user.
- 4) In order to promote international uniformity, IEC National Committees undertake to apply IEC Publications transparently to the maximum extent possible in their national and regional publications. Any divergence between any IEC Publication and the corresponding national or regional publication shall be clearly indicated in the latter.
- 5) IEC itself does not provide any attestation of conformity. Independent certification bodies provide conformity assessment services and, in some areas, access to IEC marks of conformity. IEC is not responsible for any services carried out by independent certification bodies.
- 6) All users should ensure that they have the latest edition of this publication.
- 7) No liability shall attach to IEC or its directors, employees, servants or agents including individual experts and members of its technical committees and IEC National Committees for any personal injury, property damage or other damage of any nature whatsoever, whether direct or indirect, or for costs (including legal fees) and expenses arising out of the publication, use of, or reliance upon, this IEC Publication or any other IEC Publications.
- 8) Attention is drawn to the Normative references cited in this publication. Use of the referenced publications is indispensable for the correct application of this publication.
- 9) Attention is drawn to the possibility that some of the elements of this IEC Publication may be the subject of patent rights. IEC shall not be held responsible for identifying any or all such patent rights.

International Standard IEC 62047-36 has been prepared by subcommittee 47F: Micro-electromechanical systems, of IEC technical committee 47: Semiconductor devices.

The text of this International Standard is based on the following documents:

FDIS	Report on voting
47F/329/FDIS	47F/334/RVD

Full information on the voting for the approval of this International Standard can be found in the report on voting indicated in the above table.

This document has been drafted in accordance with the ISO/IEC Directives, Part 2.

A list of all parts in the IEC 62047 series, published under the general title *Semiconductor devices – Micro-electromechanical devices*, can be found on the IEC website.

The committee has decided that the contents of this document will remain unchanged until the stability date indicated on the IEC website under "<http://webstore.iec.ch>" in the data related to the specific document. At this date, the document will be

- reconfirmed,
- withdrawn,
- replaced by a revised edition, or
- amended.

A bilingual version of this publication may be issued at a later date.

**IMPORTANT – The 'colour inside' logo on the cover page of this publication indicates that it contains colours which are considered to be useful for the correct understanding of its contents. Users should therefore print this document using a colour printer.**

## INTRODUCTION

Piezoelectric MEMS technology belongs to an interdisciplinary field founded on a wide range of element technologies including piezoelectric thin film materials, thin film deposition and microfabrication processes, device design, and system formulation. Along with the increased sophistication of MEMS functionality, research on MEMS applications for piezoelectric thin films, such as  $\text{Pb}(\text{Zr,Ti})\text{O}_3$  (PZT) or AlN, has become increasingly popular in recent years. MEMS piezoelectric thin films have the capability of configuring simple compact devices that have a lower power consumption, higher sensitivity, and quicker response than conventional bulk-type, electrostatic, or electromagnetic thin films. However, their device performance is greatly affected by the properties of the thin film materials.

Several test methods for thin film materials have been established to date. Among these, the overriding property that determines device performance is the material's piezoelectric property. Standardization of IEC 62047-30 (*Semiconductor devices – Micro-electromechanical devices – Part 30: Measurement methods of electro-mechanical conversion characteristics of MEMS piezoelectric thin film*) has been promoted for the purpose of precisely measuring and evaluating MEMS piezoelectric thin films using simply structured test pieces and inexpensive equipment.

In order to realize a viable MEMS piezoelectric thin film, it is essential to gain a clear understanding of how its piezoelectric properties change as a result of the environmental stress of temperature and humidity, and degradation in the piezoelectric material over time at its surfaces and interfaces. Achieving a viable MEMS piezoelectric thin film will also require a clear understanding of dielectric withstand for the electrical stress of a voltage (electric field) higher than the drive voltage (electric field) used for normal operations.

The following summarizes the features of this standard.

- The degree of degradation in a device under test (DUT) is evaluated by measuring the piezoelectric properties of the DUT before and after applying the environmental stress of temperature and humidity using the measurement methods in IEC 62047-30.
- Test conditions for moist heat and dielectric withstand tests are derived from existing standards for semiconductor devices and fixed capacitors of ceramic dielectric.
- The dielectric withstand property is evaluated by measuring the leakage current under the DC bias voltage.

## **SEMICONDUCTOR DEVICES – MICRO-ELECTROMECHANICAL DEVICES –**

### **Part 36: Environmental and dielectric withstand test methods for MEMS piezoelectric thin films**

#### **1 Scope**

This part of IEC 62047 specifies test methods for evaluating the durability of MEMS piezoelectric thin film materials under the environmental stress of temperature and humidity and under electrical stress, and test conditions for appropriate quality assessment. Specifically, this document specifies test methods and test conditions for measuring the durability of a DUT under temperature and humidity conditions and applied voltages. It further applies to evaluations of converse piezoelectric properties in piezoelectric thin films formed primarily on silicon substrates, i.e., piezoelectric thin films used as actuators.

This document does not cover reliability assessments, such as methods of predicting the lifetime of a piezoelectric thin film based on a Weibull distribution.

#### **2 Normative references**

The following documents are referred to in the text in such a way that some or all of their content constitutes requirements of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

IEC 62047-30, *Semiconductor devices – Micro-electromechanical devices – Part 30: Measurement methods of electro-mechanical conversion characteristics of MEMS piezoelectric thin film*

IEC 60068-2-14:2009, *Environmental testing – Part 2-14: Tests – Test N: Change of temperature*